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| APPLICATION NO.   | FILING DATE    | FIRST NAMED INVENTOR | ATTORNEY DOCKET NO.     | CONFIRMATION NO |
|---|----------------|----------------------|-------------------------|-----------------|
| 10/604,891  | 08/25/2003     | Takuji TANAKA        | 031032                  | 1890            |
| 38834 7.  | 590 04/13/2006 | r                    | EXAM                    | INER            |
| WESTERMAN, HATTORI, DANIELS & ADRIAN, LLP<br>1250 CONNECTICUT AVENUE, NW<br>SUITE 700<br>WASHINGTON, DC 20036 |                |                      | LEE, EUGENE             |                 |
|   |                |                      | ART UNIT                | PAPER NUMBER    |
|   |                |                      | AKTONII                 | PAPER NUMBER    |
|   |                |                      | 2815                    |                 |
|   |                |                      | DATE MAILED: 04/13/2006 |                 |

Please find below and/or attached an Office communication concerning this application or proceeding.

|   | Application No.   | Applicant(s)   |
|---|---|--|
|   | 10/604,891  | TANAKA, TAKUJI   |
| Office Action Summary   | Examiner  | Art Unit   |
|   | Eugene Lee  | 2815   |
| The MAILING DATE of this communication app<br>Period for Reply  | ears on the cover sheet with t  | he correspondence address  |
| A SHORTENED STATUTORY PERIOD FOR REPLY WHICHEVER IS LONGER, FROM THE MAILING DA  - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication.  - If NO period for reply is specified above, the maximum statutory period wa  - Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b). | ATE OF THIS COMMUNICAT 36(a). In no event, however, may a reply to the second will expire SIX (6) MONTHS, cause the application to become ABAND | TON.  De timely filed  from the mailing date of this communication.  ONED (35 U.S.C. § 133). |
| Status  | •   |  |
| 1)⊠ Responsive to communication(s) filed on <u>30 Ja</u>  | anuary 2006.  |  |
| 2a)⊠ This action is <b>FINAL</b> . 2b)☐ This  | action is non-final.  |  |
| 3) Since this application is in condition for allowar closed in accordance with the practice under E  |   |  |
| Disposition of Claims   | •   |  |
| 4) ☐ Claim(s) 1 and 13-16 is/are pending in the app 4a) Of the above claim(s) is/are withdray 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 1 and 13-16 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and/or  | vn from consideration.  |  |
| Application Papers  | ••  | •  |
| 9) The specification is objected to by the Examine  | r.  |  |
| 10) The drawing(s) filed on is/are: a) acce   |   | he Examiner.   |
| Applicant may not request that any objection to the   | drawing(s) be held in abeyance.   | See 37 CFR 1.85(a).  |
| Replacement drawing sheet(s) including the correct  |   |  |
| Priority under 35 U.S.C. § 119  |   |  |
| 12) ☐ Acknowledgment is made of a claim for foreign  a) ☐ All b) ☐ Some * c) ☐ None of:  1. ☐ Certified copies of the priority documents  2. ☐ Certified copies of the priority documents  3. ☐ Copies of the certified copies of the priority application from the International Bureau  | s have been received. s have been received in Applirity documents have been rec<br>u (PCT Rule 17.2(a)).  | cation No<br>eived in this National Stage  |
| * See the attached detailed Office action for a list  | or the certified copies not rec   | eiveu.   |
| ·   | •   | •  |
|   |   |  |
| Attachment(s)  1) Notice of References Cited (PTO-892)  | 4) Interview Sumr   | nary (PTO-413)   |
| 2) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date  | Paper No(s)/Ma  | nal Patent Application (PTO-152)   |

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#### **DETAILED ACTION**

### Claim Rejections - 35 USC § 103

- 1. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
  - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 2. Claims 1, and 13 are rejected under 35 U.S.C. 103(a) as being unpatentable over Kasai 5,821,594 in view of Wu 6,180,988 B1. Kasai discloses (see, for example, FIG. 4) a semiconductor device comprising a gate oxide layer (gate insulation film) 53, gate electrode 54, n+- diffusion layer (source, drain) 58, silicon oxide layer (low permittivity region) 59, silicon oxide layer (first film) 55, and etch stop layer (second film) 56. Kasai does not disclose said low permittivity region being made of a lower permittivity material as compared to said sidewall film. However, Wu discloses (see, for example, FIG. 8) a semiconductor device comprising air gaps (low permittivity region) 22. In column 4, lines 26-27, Wu discloses the air gaps reduce the effect of gate fringe capacitance. Therefore, it would have been obvious to one of ordinary skill in the art at the time of invention to have said low permittivity region being made of a lower permittivity material as compared to said sidewall film in order to reduce the effect of gate fringe capacitance.

Regarding claim 13, see, for example, FIG. 4 wherein Kasai discloses an etch stop layer (third film) 56.

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3. Claims 14 thru 16 are rejected under 35 U.S.C. 103(a) as being unpatentable over Kasai '594 in view of Wu '988 B1 as applied to claims 1, and 13 above, and further in view of Lee 6,251,737 B1. Kasai in view of Wu does not disclose a part of a side wall lower portion of said gate is removed to have said low permittivity region formed into a notched shape. However, Lee discloses (see, for example, FIG. 1H) a MOS transistor comprising a gate polysilicon layer 116, and air spacers 136. The air spacers are formed in a notch underneath the gate polysilicon layer. In column 5, lines 60-66, Lee discloses that signal transmission delay is reduced, and the operating speed of the device is increased. Therefore it would have been obvious to one of ordinary skill in the art at the time of invention to have a part of a side wall lower portion of said gate is removed to have said low permittivity region formed into a notched shape in order to reduce signal transmission delay, and increase operating speed.

#### Response to Arguments

4. Applicant's arguments filed 1/30/06 have been fully considered but they are not persuasive.

Regarding the applicant's argument on page 6 of the amendment filed 1/30/06 that the mere fact that references may be modified in the manner suggested by the Examiner does not make the modification obvious unless the prior art suggested the desirability of the modification, this argument is not persuasive. It must be recognized that any judgment on obviousness is in any sense necessarily a reconstruction based upon hindsight reasoning. But so long as it takes into account only knowledge which was within the level of ordinary skill at the time the invention was made, and does not include knowledge gleaned only from the Applicant's

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disclosure, such a reconstruction is proper. In re McLaughlin, 443 F. 2d 1392; 170 USPQ 209 (CCPA 1971). In this case, Wu gives a clear motivation (see, for example, column 4, lines 26, 27) to use air gaps for a MOSFET. Such an air gap, when included in the embodiment of Kasai, would provide a clear separation between the gate electrode and the substrate 51, and thereby reduce fringe capacitance to a greater extent than would a material. Also, the reduction of fringe capacitance would occur in an area (i.e. between the gate electrode and substrate) where fringe capacitance would be most prevalent (see paragraph [0014] of applicant's specification), further justifying the appropriateness of the combination.

#### Conclusion

THIS ACTION IS MADE FINAL. Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

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## INFORMATION ON HOW TO CONTACT THE USPTO

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Eugene Lee whose telephone number is 571-272-1733. The examiner can normally be reached on M-F 8-5.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Kenneth Parker can be reached on 571-272-2298. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Eugene Lee April 6, 2006

> EUGENE LEE PRIMARY EXAMINER